

## IN THE CLAIMS

Please cancel Claims 1-6 without prejudice and without disclaimer of subject matter.

Please add new Claims 7-9 to read as follows.

--7. (New) A manufacturing method of an electron source panel having a plurality of electron emitting devices disposed on a substrate, comprising the steps of:

measuring electron emission characteristics of each of the electron emitting devices and setting a characteristics adjustment target value;

applying a plurality of characteristics shift voltages having discrete values to some of the electron emitting devices, measuring electron emission characteristics of these electron emitting devices and creating a characteristics adjustment table for each of the values in accordance with an average of change rates of measured electron emission characteristics of these electron emitting devices; and

selecting a predetermined characteristics shift voltage value from the plurality of characteristics shift voltage values by referring to the characteristics adjustment table created for each of the electron emitting devices and applying the predetermined characteristics shift voltage to the electron emitting devices to shift the characteristics toward the characteristics adjustment target value.

8. (New) A method according to Claim 7, further comprising, after shifting of the characteristics toward the characteristics adjustment target value, a step of

monitoring a change of the electron emission characteristics to revise a characteristics shift condition.

9. (New) A method according to Claim 8, wherein the characteristics shift condition is revised by a step of judging whether the change rates of the electron emission characteristics after an initial characteristics shift pulse is applied, fall in a predetermined range and a step of revising a pulse width of the predetermined characteristics shift voltage if the change rates do not fall in the predetermined range.--